
**Surface chemical analysis — Depth
profiling — Non-destructive depth
profiling of nanoscale heavy metal
oxide thin films on Si substrates with
medium energy ion scattering**

*Analyse chimique des surfaces — Profilage d'épaisseur — Profilage
d'épaisseur non destructif de films minces d'oxydes de métaux lourds
à l'échelle nanométrique sur des substrats de Si par diffusion d'ions de
moyenne énergie*





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